

10/560126

IAP810000000 09 DEC 2005
PATENT

SHIGA7.037APC

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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|----------------|---|
| Applicant | : TAMURA, K. et al. |
| Appl. No. | : Unknown |
| Filed | : Herewith |
| For | : POSITIVE RESIST COMPOSITION, RESIST LAMINATES AND PROCESS FOR FORMING RESIST PATTERNS |
| Examiner | : Unknown |
| Group Art Unit | : Unknown |

PRELIMINARY AMENDMENT

Mail Stop Amendment

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Dear Sir:

Preliminary to examination on the merits, please amend the above-captioned U.S. National Phase Application as follows:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper.

Remarks/Arguments begin on page 6 of this paper.